

Interaction between point defects in the Si-SiO₂ system during the process of its formation

Kropman, Daniel; Kärner, T.; Samoson, Ago; Heidmaa, I.; Ugaste, Ülo; **Mellikov, Enn** Defect and Diffusion Forum 2001 / p. 1737-1744 <https://www.sciencedirect.com/science/article/abs/pii/S0168583X0100862X>